

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Masuda et al.
Appl. No.	:	10/564,510
Filed	:	January 12, 2006
For	:	POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Chu, John S Y
Group Art Unit	:	1752

**SUBMISSION WITH RCE****Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **December 12, 2007**, and the Advisory Action mailed March 24, 2008, please consider the following amendment and remarks:

**Amendments to the claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 5 of this paper.